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**AMENDMENT TRANSMITTAL LETTER**Docket No.  
T2171.0196Application No.  
09/873,580Filing Date  
June 4, 2001Examiner  
F. ToledoArt Unit  
2823

Applicant(s): Harumitsu Fujita et al.

Invention: MULTI-VOLTAGE LEVEL SEMICONDUCTOR DEVICE AND ITS MANUFACTURE

**TO THE COMMISSIONER FOR PATENTS**

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

CLAIMS AS AMENDED					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
Total Claims	10	- =		X	
Independent Claims	2	- =		X	

Multiple Dependent Claims (check if applicable) 

Other fee (please specify):

**TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:** Large Entity Small Entity No additional fee is required for this amendment. Please charge Deposit Account No. \_\_\_\_\_ in the amount of \$ \_\_\_\_\_.  
A duplicate copy of this sheet is enclosed. A check in the amount of \$ \_\_\_\_\_ to cover the filing fee is enclosed. The Commissioner is hereby authorized to charge and credit Deposit Account No. 04-1073 as described below. A duplicate copy of this sheet is enclosed. Credit any overpayment. Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.  
Michael J. Scheer

Attorney Reg. No. 34,425

Dated: November 4, 2002

DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP  
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**FEE TRANSMITTAL  
for FY 2002**

Patent fees are subject to annual revision.

 Applicant claims small entity status. See 37 CFR 1.27**TOTAL AMOUNT OF PAYMENT** (\$ 400.00)**Complete if Known**

Application Number	09/873,580
Filing Date	June 4, 2001
First Named Inventor	Harumitsu Fujita et al.
Examiner Name	F. Toledo
Group Art Unit	2823
Attorney Docket No.	T2171.0196

**METHOD OF PAYMENT (check all that apply)**

Check  Credit Card  Money Order  Other  None  
 Deposit Account

Deposit Account Number 04-1073

Deposit Account Name Dickstein Shapiro Morin &amp; Oshinsky LLP

## The Commissioner is hereby authorized to: (check all that apply)

Charge fee(s) indicated below  Credit any overpayments  
 Charge any additional fee(s) during the pendency of this application  
 Charge fee(s) indicated below, except for the filing fee to the above-identified deposit account.

**FEE CALCULATION (continued)****3. ADDITIONAL FEES**

Large Entity	Small Entity	Fee Description	Fee Paid
Fee Code	Fee (\$)	Fee Code	Fee (\$)
105	130	205	65
127	50	227	25
139	130	139	130
147	2,520	147	2,520
112	920*	112	920*
113	1,840*	113	1,840*
115	110	215	55
116	400	216	200
117	920	217	460
118	1,440	218	720
128	1,960	228	980
119	320	219	160
120	320	220	160
121	280	221	140
138	1,510	138	1,510
140	110	240	55
141	1,280	241	640
142	1,280	242	640
143	460	243	230
144	620	244	310
122	130	122	130
123	50	123	50
126	180	126	180
581	40	581	40
146	740	246	370
149	740	249	370
179	740	279	370
169	900	169	900
Other fee (specify)			
*Reduced by Basic Filing Fee Paid		<b>SUBTOTAL (3)</b>	(\$ 400.00)

\*\* or number previously paid, if greater; For Reissues, see above

SUBMITTED BY		Complete (if applicable)	
Name (Print/Type)	Michael J. Scheer	Registration No. (Attorney/Agent)	34,425
Signature	<i>Michael J. Scheer</i>	Date	November 4, 2002



Docket No.: T2171.0196

(PATENT)

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:  
Harumitsu Fujita

Application No.: 09/873,580

Group Art Unit: 2823

Filed: June 4, 2001

Examiner: F. Toledo

For: MULTI-VOLTAGE LEVEL  
SEMICONDUCTOR DEVICE AND ITS  
MANUFACTURE

AMENDMENT

**Box Non-Fee Amendment**  
Commissioner for Patents  
Washington, DC 20231

Dear Sir:

In response to the Office Action mailed June 5, 2002, please amend the above-identified U.S. patent application as follows:

In the Claims:

Cancel claims 1, 2, 5 and 6.

19. (New) A method of manufacturing a semiconductor device comprising at least first and second MOS transistors, said method comprising:

providing a semiconductor substrate having at least first and second active regions of a first conductivity type;

forming a gate oxide layer having a first thickness onto at least said first and second active regions;

forming an electrode layer onto said gate oxide layer;